

**Search Notes**

Application/Control No.

10/609,476

Examiner

Stephen W. Smoot

Applicant(s)/Patent under  
Reexamination

FUJIOKA ET AL.

Art Unit

2813

**SEARCHED**

Class	Subclass	Date	Examiner
438	240	8/16/2004	SWS
438	253	8/16/2004	SWS
438	255	8/16/2004	SWS
438	396	8/16/2004	SWS
438	398	8/16/2004	SWS
438	591	8/16/2004	SWS
438	785	8/16/2004	SWS
Updated	Above	1/26/2005	SWS

**INTERFERENCE SEARCHED**

Class	Subclass	Date	Examiner
Same as Above		1/26/2005	SWS

**SEARCH NOTES  
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
Key Words: Atomic Layer Deposition - ALD, ALE; Capacitor Dielectric - Tantalum, Hafnium, Zirconium.	8/16/2004	SWS
Updated Above Search	1/26/2005	SWS
plus Chemical Vapor Deposition - CVD; Oxidizing Gas; Metal.	1/26/2005	SWS
Search Tools - EAST (attached): USPAT; US PG PUBS; Derwent; EPO; JPO; IBM TDB	8/16/2004 & 1-26-05	SWS